- 13. The semiconductor structure of claim 10, wherein the compositionally graded Group III-nitride alloy comprises $In_xAl_{1-x}N$ that is graded between two portions of the Group III-nitride alloy between two values of x, where $0.0 \le x \le 1.0$.
- 14. The semiconductor structure of claim 13, wherein the Group III-nitride alloy layer comprises $In_xAl_{1-x}N$, where $0.6 \le x \le 0.8$.
 - 15. A photovoltaic layer for a solar cell comprising: a layer of a compositionally graded Group III-nitride alloy.
- 16. The photovoltaic layer for a solar cell of claim 15, wherein the compositionally graded Group III-nitride alloy layer comprises $In_xGa_{1-x}N$ that is graded between two portions of the Group III-nitride alloy layer between two values of x, where $0.0 \le x \le 1.0$.
- 17. The photovoltaic layer for a solar cell of claim 16, wherein the compositionally graded Group III-nitride alloy layer comprises $In_xGa_{1-x}N$, where $0.25 \le x \le 0.45$.
- 18. The photovoltaic layer for a solar cell of claim 15, wherein the compositionally graded Group III-nitride alloy layer comprises $\ln_x Al_{1-x}N$ that is graded between two portions of the Group III-nitride alloy layer between two values of x, where $0.0 \le x \le 1.0$.
- 19. The photovoltaic layer for a solar cell of claim 18, wherein the compositionally graded Group III-nitride alloy layer comprises $In_xAl_{1-x}N$, where $0.6 \le x \le 0.8$.

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